## ALD for Optical Coatings – Materials and Applications

ALD for Industry // March 20, 2019

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#### Outline

- Beneq company presentation
- ALD for optics; from properties to structures
- Examples and case studies
- ALD tools for optics



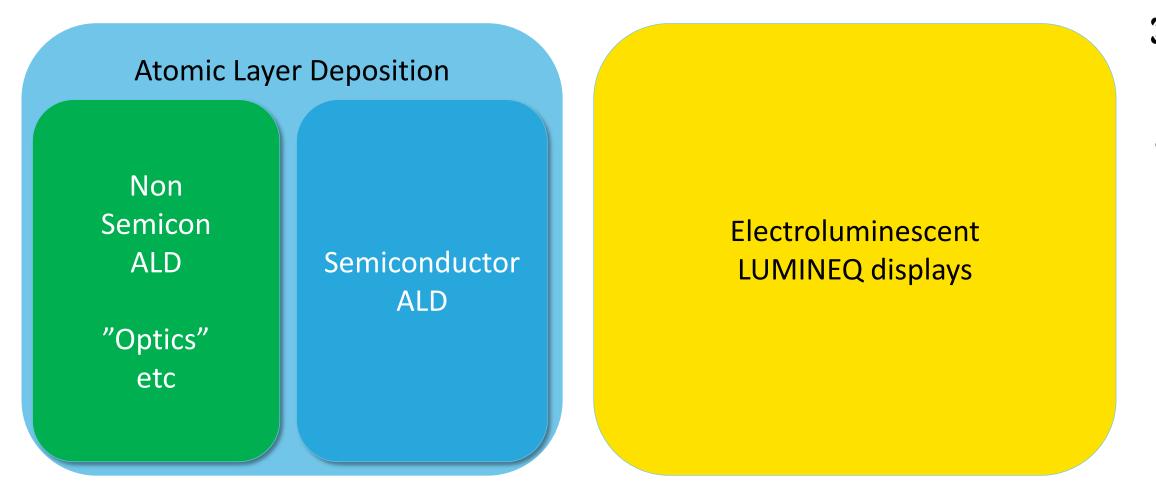
#### **Beneq – Industrial ALD solutions**



- Established in 2005, FINLAND
- Worldwide operations
- Long history in ALD
- One of the largest cleanrooms in Europe
- 2000 m2 cleanroom / 40 ALD reactors

- We are helping customers in:
- Development services
- Coating services
- ALD tool engineering
- Customer care

#### **Business lines**



#### Atlas of ALD



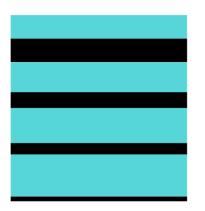
## **ALD for optics**

Desired properties from coating method for optical coatings	Characteristics of ALD
Films optically suitable (for application)	Dense, stoichiometric, non-absorbing transparent films; Absorbing films (e.g. metals)
Stability of coatings	Dense, stoichiometric films - typically stable
Precise thickness of coated layers	"Digital" layer-by-layer thickness control
Sharp interfaces	Interfaces typically sharp depending on material selection, low interdiffusion between layers
Complex shapes can be coated uniformly	Extremely conformal films
Low cost per coated piece	Can be performed in a batch reactor

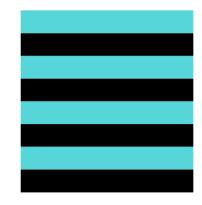
#### **Optical coatings by ALD – basic structures**



Single films:  $Al_2O_3$ ,  $TiO_2$ ,  $SiO_2$ ,  $HfO_2$ ,  $Ta_2O_5$ , ZnO, ZnS, AlN ...



Gradient films:  $Al_2O_3$ -Ti $O_2$ , Ti $O_2$ -Si $O_2$ ,  $Al_2O_3$ -Hf $O_2$ , ...

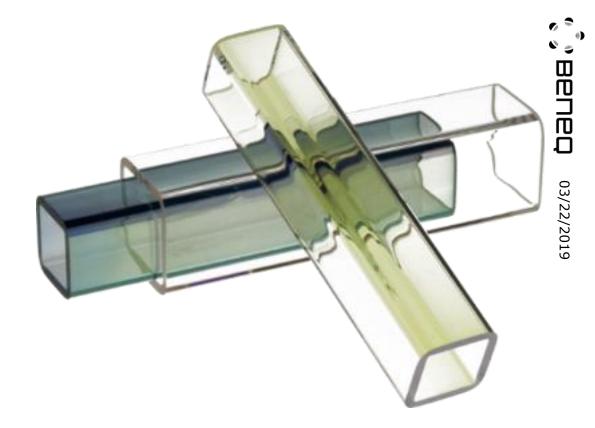


Laminate films:  $Al_2O_3$ -Ti $O_2$ , Ti $O_2$ -Si $O_2$ ,  $Al_2O_3$ -Hf $O_2$ , ...



## **ALD Optical applications**

- Dielectric mirrors
- Anti-reflective coatings
- Filters
- Complex optical systems
- Night vision devices
- Micro displays
- Lasers
- Space applications
- Machine vision
- Image sensors
- Lense structures
- Tubes, wires, channels, fibers



#### **ALD processes for optics**

- Vacuum, low pressure 1 bar, torr, hPa
- Plasma PEALD (rotary batch ALD tool or single wafer process)
- Thermal ALD (single wafer or batch process)
- Spatial ALD (roll-to-roll or rotary ALD)
- Most common optical materials: Al2O3, TiO2, SiO2:Al, ZnO, ZnO:Al, ZnS
- 3D substrates

Tubular objects, inside/outside surfaces

Double side coatings, flat substrates

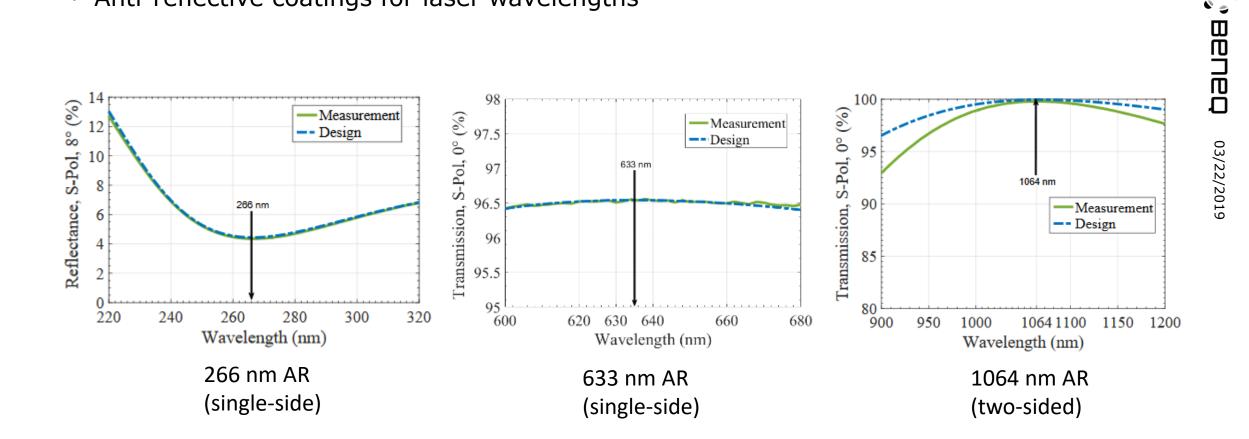
Nanofabrication coatings

Trench filling

High aspect ratio objects

#### Example – single films in a filter stack (1/3)

Anti-reflective coatings for laser wavelengths

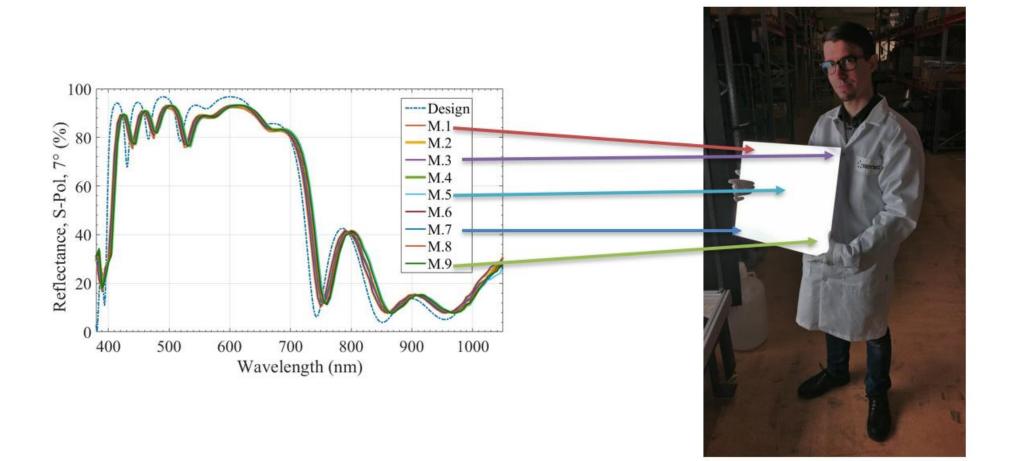


#### Example – single films in a filter stack (2/3)

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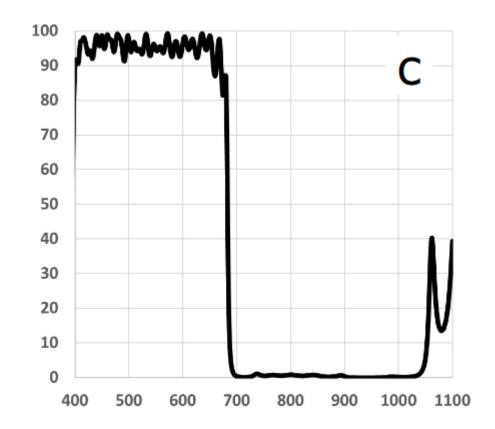
- Mirror-like coating on large glass sheets (1,5 µm)
- Made with spatial ALD (Beneq SCS1000)



#### Example – single films in a filter stack (3/3)

- Single films of Al2O3, TiO2
- Producing an optical stack
- 77 layers, 5.5 µm
- Deposited on curved glass cylinders



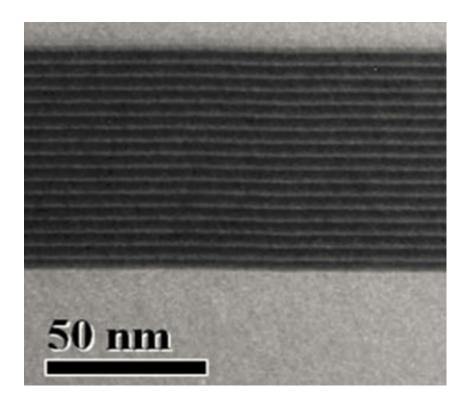


Wavelength vs. Transmission of the filter stack

#### Example – single films in a filter stack (3/3)

- Al2O3 AlxTiyOz TiO2
- + 77 layers alternating Al2O3/TiO2 = 5.5  $\mu m$

- TiO2 in-situ modification (Al or Si)
- Interface modification by Al2O3
- Cutting layer: to prevent crystallization of TiO2 by 0,6 nm Al2O3 every 4 nm

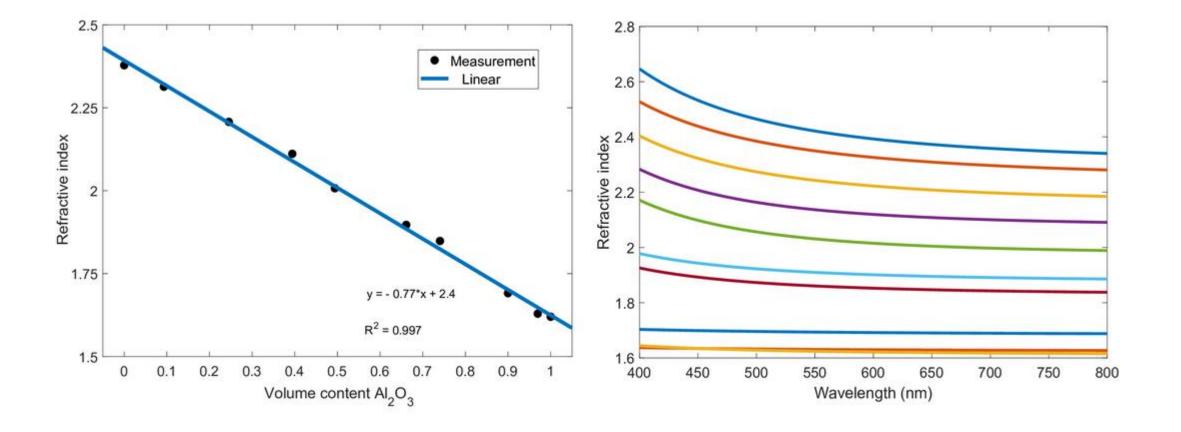


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#### **Example – Laminated films**

- Refractive index behaviour in laminated Al2O3-TiO2 system
- Direct consequence: ability to tailor refractive index to application

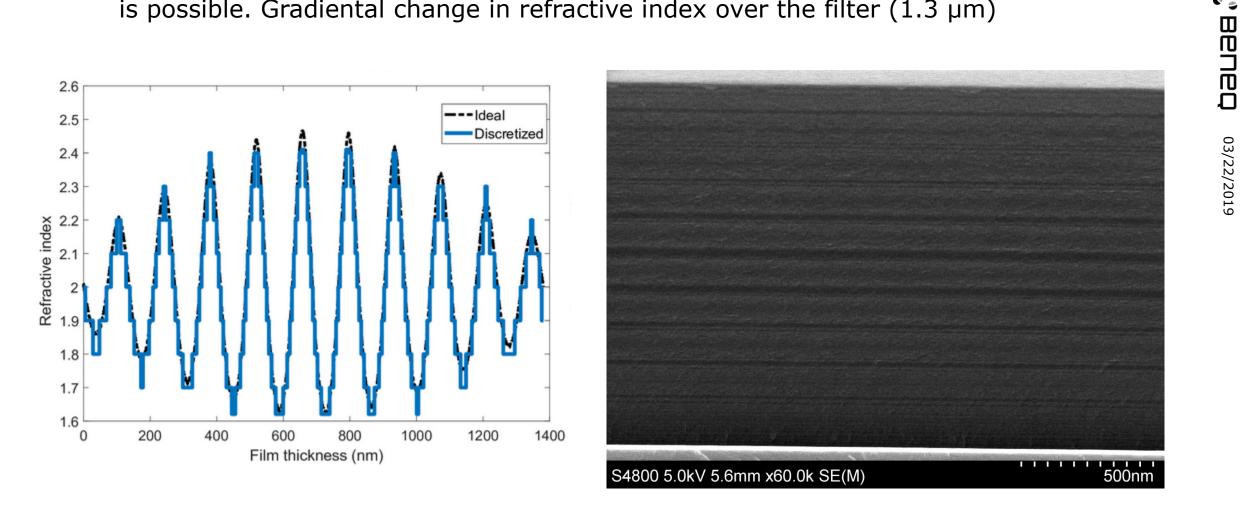


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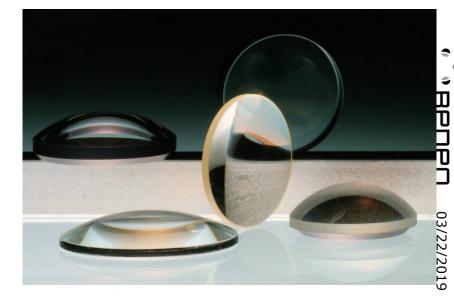
#### **Example – graded structure**

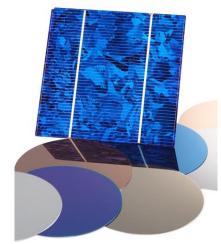
• Because of linearity, tailored indices manufactured so that an apodized rugate filter is possible. Gradiental change in refractive index over the filter (1.3  $\mu$ m)



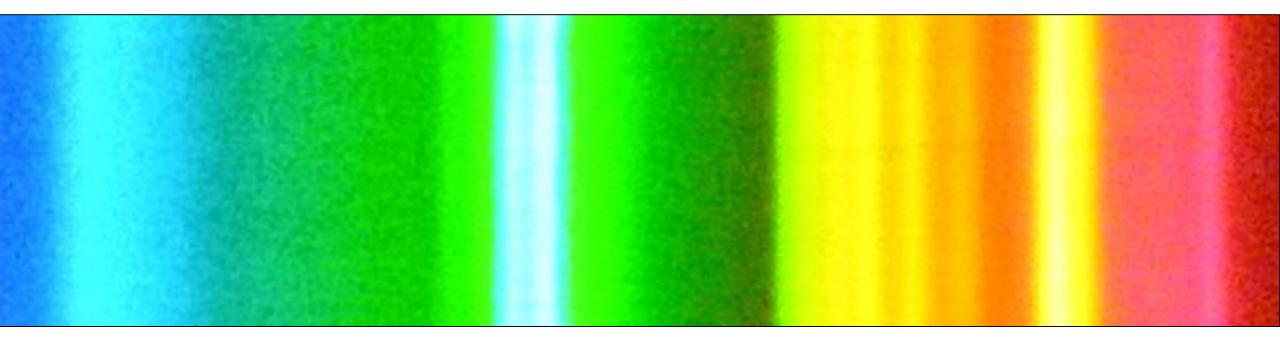
## **ALD for IR optics**

- ALD available for multiple imaging applications (hyperspectral, thermal)
- Digital and stable ALD process: management of coating thickness for target wavelength (filter thickness <-> wavelength)
- Many of the traditional ALD lossless VISregion film materials extend well to the IR
  - ZnS –> 25 µm
  - $AI_2O_3 -> 9 \ \mu m$
  - TiO<sub>2</sub> -> 12 μm
  - SiO<sub>2</sub> -> 8 μm





#### **Filling of Diffractive Gratings**



#### The challenge

The customer was looking for ways to adjust the optical performance of their diffractive gratings and to keep the gratings free from debris.

#### The customer

A leading optical system manufacturer

#### **Beneq solution**

Beneq used ALD to fill the grating structure completely with a high refractive index material to boost the optical performance. The resulting structure is essentially flat, which helps keep the structure clean.

#### **ALD tools for optics**



#### P400A – Industrial ALD batch for optics



- Production-proven Batch ALD system
- Typical substrate formats: sheets, 3Dparts, wafers
- Typical substrate materials: glass, metal, silicon, ceramic, polymer
- Typical coating materials:  $Al_2O_3$ ,  $TiO_2$ , ZnO, SiO<sub>2</sub>:Al, Ta<sub>2</sub>O<sub>5</sub>, TiN, AlN, ZnS...
- Typical coating thickness 5nm-5µm
- Process pressure ~1mbar
- Process temperature 80...500C
- Typical reaction chamber coating volume 240x240x360 mm

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#### **Batch coating**

- Large reactor space
- Shelves/sample holders can be fitted depending on application

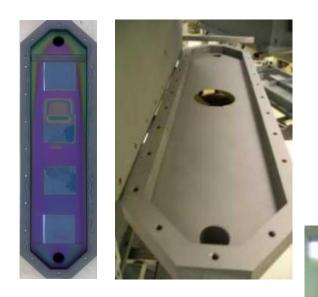


A Beneq P800 reaction chamber for deposition on sheet-like substrates

Fig. 4. Example of the TiO<sub>2</sub> batch for uniform  $(\pm 2\%)$  coatings, 36 shelves 240×500 (mm), double-sided coatings (8 m<sup>2</sup> of a film).<sup>1</sup>

<sup>1</sup>Maula, J. Atomic Layer Deposition for industrial optical coatings. 2010. Chinese optics Letters Vol. 8, Supplement.

#### Wide variety of reaction chambers (P400A)

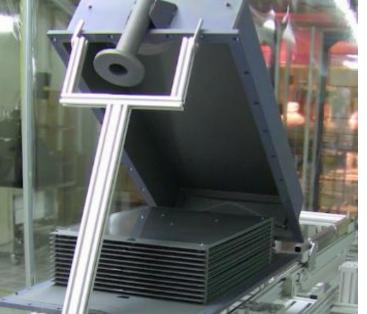




**Small (fast):**W=170mm H=145mm L=540mm / W=165mm H=25mm L=670mm

**Medium 0,7 m long:** 250x250x700 mm<sup>3</sup>, coating volume 240x240x500 mm<sup>3</sup>

**Large:** W=374mm H=25mm L=840mm





#### Thank you for your attention!



#### **BENEQ - Turning Innovations into Success**